

$$\sum m \alpha^2$$

## PATENT

Atty. Dkt. AMAT/4213.P1/MASK/MASK-ETCH/ARNOLD S

1765-

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

~~TRADE~~  
In re Application of:  
Buie, et al.

Serial No.: 10/024,958

Confirmation No.: 3439

Filed: December 18, 2001

# For: Etch Process for Photolithographic Reticle Manufacturing With Improved Etch Bias

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Group Art Unit: 1765

Examiner: Kin-Chan Chen

<p style="text-align: center;"><b>CERTIFICATE OF MAILING</b></p> <p style="text-align: center;"><b>37 CFR 1.8</b></p> <p>I hereby certify that this correspondence is being deposited on April 12, 2004 with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450.</p> <p><u>April 12, 2004</u> Date</p> <p><u><i>B. k. Ehr</i></u> Signature</p>
--

Dear Sir:

## **SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT**

The Applicants, and the Attorney who signs below on the basis of the information supplied by the inventor and the information in his file, submit herewith patents, publications, or other information of which they are aware, which may be material to the examination of this application and in respect of which there may be a duty to disclose in accordance with 37 CFR § 1.56.

While the information submitted in this Supplemental Information Disclosure Statement may be material pursuant to 37 CFR § 1.56, it is not intended to constitute an admission that any patent, publication, or other information referred to therein is prior art for this invention unless specifically designated as such.

In accordance with 37 CFR § 1.97, this Supplemental Information Disclosure Statement is not to be construed as a representation that a search has been made or that no other possibly material information as defined under 37 CFR § 1.56(a) exists.

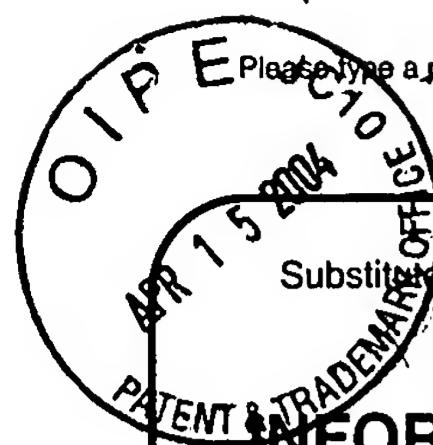
The patents and/or publications submitted herewith are set forth on the attached Form PTO-1449.

Applicants certify that all references submitted with this disclosure were first cited in a communication from a foreign patent office dated February 19, 2004, which communication is enclosed, not more than three months prior to the filing of this Supplemental Information Disclosure Statement.

If the sum of \$180.00 is due under 37 CFR § 1.17(p) pursuant to § 1.97, the Commissioner is hereby authorized to charge this fee, and any other fee necessary to make this submission timely, to the Deposit Account No. 20-0782/AMAT/4213.P1/BKH.

Respectfully submitted,

  
\_\_\_\_\_  
Brian K. Hrna  
Registration No. 41,852  
MOSER, PATTERSON & SHERIDAN, L.L.P.  
3040 Post Oak Blvd. Suite 1500  
Houston, TX 77056  
Telephone: (713) 623-4844  
Facsimile: (713) 623-4846  
Attorney for Applicant(s)



Please type a plus sign (+) inside this box →

PTO/SB/08a (08-03)

Approved for use through 07/31/2006. OMB 0651-0031  
U.S. Patent and Trademark Office: U.S. DEPARTMENT OF COMMERCE  
Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it displays a valid OMB control number.

Substitute for form 1449A/PTO

## SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use as many sheets as necessary)

Sheet 1		of 1	Application Number	10/024,958
			Filing Date	DECEMBER 18, 2001
			First Named Inventor	BUIE, ET AL.
			Group Art Unit	1765
			Examiner Name	KEN-CHAN CHEN
			Attorney Docket Number	AMAT/4213.P1/MASK/MASK-ETCH/ARNOLD S
			Submission Date	April 12, 2004

### NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T <sup>2</sup>
	A1	PCT Search Report for PCT/US03/11549, dated February 19, 2004 (AMAT/6991.PC)	
	A2	KWON, ET AL., "Loading Effect Parameters at Dry Etcher System and Their Analysis at Mask-to-Mask Loading and Within-Mask Loading" Proceedings of SPIE, Vol. 4562 (2002) pp. 79-87.	
	A3	FUJISAWA, ET AL. "Evaluation of NLD Mask Dry Etching System" SPIE Symposium on Photomask and X-Ray Technology VI, Yokohama, JAPAN, September (1999) Vol. 3748 pp. 147-152.	
	A4	RUHL, ET AL. "Chrome Dry Etch Process Characterization Using Surface Nano Profiling" Proceedings of SPIE, Vol. 4186 (2001) pp. 97-107.	
	A5	AOYAMA, ET AL. "Advanced Cr Dry Etching Process" SPIE Symposium on Photomask and X-Ray Technology VI, Yokohama, JAPAN, September (1999) SPIE, Vol. 3748 pp. 137-146.	

Examiner

Date Considered

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. <sup>1</sup> Applicant's unique citation designation number (optional). <sup>2</sup> See Kinds Codes of USPTO Patent Documents at [www.uspto.gov](http://www.uspto.gov) or MPEP 901.04. <sup>3</sup> Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup> For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup> Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. <sup>6</sup> Applicant is to place a check mark here if English language Translation is attached.

This collection of information is required by 37 CFR 1.97 and 1.98. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated to take 2 hours to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450. If you need assistance in completing the form, call 1-800-PTO-9199 (1-800-786-9199) and select option 2.